

Registration

Advanced Online Registration is required.

Registration Fee: Early Registration (Before Feb 16, 2015)
On-site Registration

Banquet Fee (On March 29, 2015)
(at Port of Nagoya Public Aquarium)

General

JPY 45,000
JPY 50,000

Student

JPY 15,000
JPY 20,000

JPY 10,000

JPY 10,000

* Refunds cannot be made at any reason.

Access

Centrair-Airport

(Central Japan International Airport)

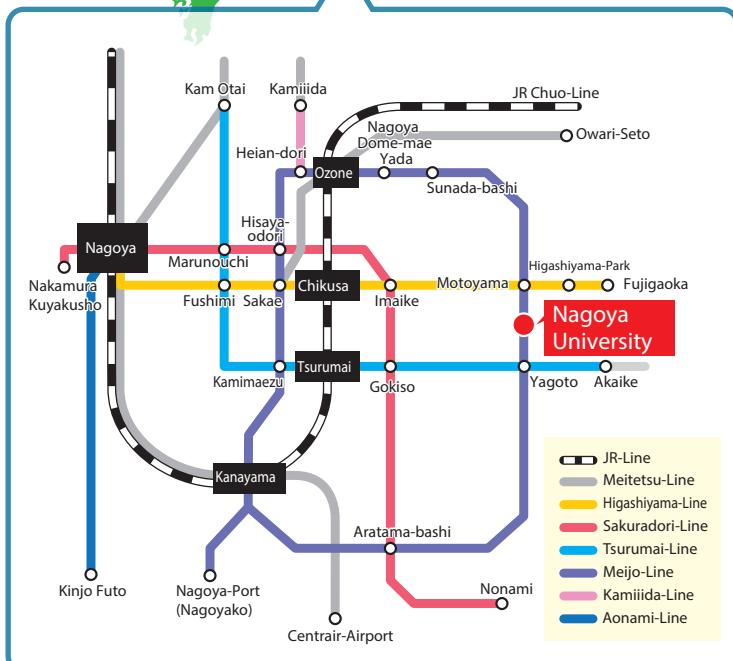
To Downtown Nagoya

- By Train
• 25 min by "Meitetsu Express" to Kanayama St.
- 30 min by "Meitetsu Express" to Nagoya St.



Narita-Airport

To Nagoya Station
By Train
1 hr. by "Narita Express" to Tokyo St.
→ 1 hr. 40 min by Shinkansen from Tokyo St.
By Air
1 hr. 10 min to Centrair
→ 30 min by "Meitetsu Express" from Centrair



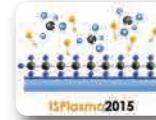
Contact

ISPlasma2015 / IC-PLANTS2015 Secretariat Y's Secretary Fields
5C, 1-1-22, Iseyama, Naka-ku, Nagoya, 460-0026 JAPAN
Phone: +81-52-332-8789 Fax: +81-52-332-8789 E-mail: isplasma@yssf.jp Website: <http://www.isplasma.jp>

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ISPlasma2015 IC-PLANTS2015

March 26-31, 2015
Nagoya University, Japan



7th International Symposium on
Advanced Plasma Science and its Applications for Nitrides and Nanomaterials /
8th International Conference on Plasma-Nano Technology & Science

Organizing Committee

Chairperson

Nagahiro Saito, Nagoya University

Vice-Chairperson

Keiji Nakamura, Chubu University
Akihiro Wakahara, Toyohashi University of Technology
Noritsugu Umehara, Nagoya University

Sponsored by : The Japan Society of Applied Physics, ISPlasma2015 / IC-PLANTS2015 Organizing Committee

Co-sponsored by : Nagoya University, Nagoya Institute of Technology, Meijo University, Chubu University,

Aichi Science & Technology Foundation,
The Japan Society of Plasma Science and Nuclear Fusion Research,
The Japanese Association for Crystal Growth

ISPlasma/IC-PLANTS is specialized international symposium where about 1,000 world-leading scientists and engineers can get together in the Tokai region (central Japan) to discuss latest researches in the fields of advanced plasma science, its application for processing and manufacturing of wide-bandgap materials and nanomaterials. This symposium will address issues such as global warming, resources and energy problems to which advanced plasma science and its application technologies can greatly contribute. We aim that holding of this symposium stimulates progress of plasma science and its application, and contributes to the improvement of social life.

Related Fields

Plasma Science

- Plasma Source • Modeling and Simulation • Thin Film Deposition Process • Etching Process
- Atmospheric-pressure plasma • Solution Plasma • Advanced Plasma Measuring Technology
- Plasma for Clean Energy • Plasma Biology and Medicine • Plasma for Nanotechnology

Functional Semiconductors

- Crystal Growth of GaN and Related Materials • SiC/Diamond
- Optical Devices • MBE Growth of Nitrides • Power device • Electron Devices

Nanomaterials and Micro fabrication

- Nano structured material • Catalyst/Battery • Solar Cell • Environmental materials • Micro-TAS

Surface Functionalization

- Hard coating • Thin Films by chemical process • Biosurface and biointerface • Functional thin films

Abstract Submission

Submission Deadline : Friday, Oct 17, 2014 JST

Special Issue

Selected papers will be published in a special issue of Jpn. J. Appl. Phys. (JJAP).

Instruction for submitting papers will be informed by late December.

Schedule at a glance

- | | |
|---------|---|
| Mar. 26 | • Facility Tour • Welcom Party at Nagoya University |
| Mar. 27 | • Openning • Plenary Lecture • Technical Session • Poster Session |
| Mar. 28 | • Plenary Lecture • Technical Session • Poster Session |
| Mar. 29 | • Plenary Lecture • Technical Session • Poster Session
• Banquet at Port of Nagoya Public Aquarium |
| Mar. 30 | • Plenary Lecture • Technical Session • Poster Session • Award • Closing • Excursion |
| Mar. 31 | • Excursion |

PROGRAM

Plenary Speakers

- Y. Arakawa (The Univeristy of Tokyo)
- K. Domen (The Univeristy of Tokyo)
- U. Helmersson (Linköping University)
- H. Matsunami (Kyoto University)
- M. Shiratani (Kyushu University)
- K. Sumitomo (NTT Basic Research Laboratories)

Invited Speakers

- C. C. Yang (National Taiwan University)
- H. Kondo (Nagoya University)
- Y. Koide (National Institute for Materials Science)
- T. Ohshima (Japan Atomic Energy Agency / Quantum Beam Science Directorate)
- A. Murphy (CSIRO)
- M. Kambara (The University of Tokyo)
- K. Ohwaki (Meijo University)
- S. Samukawa (Tohoku University)
- H. Akiyama (The Univeristy of Tokyo)
- S. Kwon (Seoul National University)
- M. Tokeshi (Hokkaido University)
- M. Kubo (Tohoku University)
- K. Satoh (Muroran Institute of Technology)
- R. Tero (Toyohashi University of Technology)
- K. Soga (Tokyo University of Science)